CLEANING DEVICE AND CLEANING METHOD

ABSTRACT OF THE DISCLOSURE

The invention provides a cleaning device for cleaning or rinsing a wafer disposed in a cleaning bath by cleaning fluid in the cleaning bath including a front wall that configures the cleaning bath by being in abutment with a device body and is formed with an opening corresponding to a contour of the target object; a wafer holding device being capable of holding a rear face of the target object carried into the inner side of the one side wall through the opening from the outside of the one side wall and holding the target object in a vertically upright position; and a pins provided on a circumference of the opening on an inner surface of the one side wall for defining a clearance between the wafer and the circumference of the opening by being in contact with the rear face of the target object.